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(54) Title: IN LINE WATER SCRUBBER SYSTEM FOR SEMICONDUCTOR PROCESSING

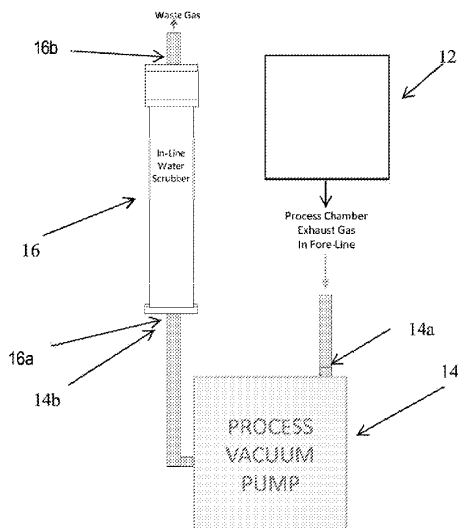


Figure 2A

(57) Abstract: A semiconductor processing system includes a vacuum pump having an inlet and an outlet, with the inlet of the vacuum pump configured to be in fluid communication with an outlet of a semiconductor reactor, and with the vacuum pump configured to output an exhaust of waste gases from the reactor at the outlet of the vacuum pump. The semiconductor processing system further includes a water scrubber system at the outlet of the vacuum pump, which has a vertical orientation relative to the pump and has an inlet and at least one mixing chamber. The inlet is in fluid communication with the outlet of the vacuum pump and the mixing chamber. The scrubber system is configured to maintain the temperature of exhaust at the output of the pump, while the exhaust is directed to the mixing chamber, and to inject water into the exhaust to remove water reactive products in the exhaust.

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